

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	("6545296").PN.	US-PGPUB; USPAT	OR	OFF	2005/01/09 16:06
L2	1	("5814839").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/01/09 16:14
L3	1402	diffus\$3 near3 reflect\$3 with substrate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 16:22
L4	10	3 and vcsel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 16:20
L5	16	3 and "372"\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 16:20
L6	84	((diffus\$3 near3 reflect\$3) or (specular near3 reflect\$3)) with substrate and semiconductor near3 laser	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 16:48
L7	2	((diffus\$3 near3 reflect\$3) or (specular near3 reflect\$3)) same (substrate near3 periodic near3 surface)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 17:00
L8	8	((diffus\$3 near3 reflect\$3) or (specular near3 reflect\$3)) and (substrate near3 periodic near3 surface)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 17:21
L9	2258	((diffus\$3 near3 reflect\$3) with (specular near3 reflect\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 17:22
L10	1601	((diffus\$3 near3 reflect\$3) near3 (specular near3 reflect\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 17:22

L11	18	10 and "372"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 19:02
L12	1	10 and "372"/43.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 19:04
L13	0	10 and "372"/98.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 19:03
L14	2	10 and "372"/99.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/09 19:03
S1	71	"438"/\$.ccls. and etch\$3 and photoelectrochemical	US-PGPUB; USPAT	OR	OFF	2003/08/18 10:16
S2	3	("438"/\$.ccls. and etch\$3 and photoelectrochemical) and vcsel	US-PGPUB; USPAT	OR	OFF	2003/07/28 07:22
S3	50	("438"/\$.ccls. and etch\$3 and photoelectrochemical) and condition\$3	US-PGPUB; USPAT	OR	OFF	2003/07/28 07:23
S4	2	((("438"/\$.ccls. and etch\$3 and photoelectrochemical) and condition\$3) and vcsel	US-PGPUB; USPAT	OR	OFF	2003/07/28 07:23
S5	13	vcsel and (specular near3 reflect\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:23
S6	360	(reduc\$4 near3 (specular near3 reflect\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:54
S7	2	((reduc\$4 near3 (specular near3 reflect\$3))) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:42
S8	10	((reduc\$4 near3 (specular near3 reflect\$3))) and (semiconductor near3 laser)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:41
S9	210	(low\$3 near3 (specular near3 reflect\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:41

S10	2	((low\$3 near3 (specular near3 reflect\$4))) and (semiconductor near3 laser\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:42
S11	0	((low\$3 near3 (specular near3 reflect\$4))) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:42
S12	97	((low\$3 near3 (specular near3 reflect\$4))) and substrate\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:43
S13	162	((reduc\$4 near3 (specular near3 reflect\$3))) and substrate\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:43
S14	56	((reduc\$4 near3 (specular near3 reflect\$3))) and substrate\$1) and laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:43
S15	1	((zero near3 order near3 (specular near3 reflect\$3))) and vcsel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:57
S16	48	(grating near3 substrate) and vcsel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 10:58
S17	0	(zero near3 order near3 (vcsel))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:08
S18	44	(zero near3 order near3 (specular near3 reflect\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:42
S19	0	vcsel and dbr and (substrate near3 low near3 reflect\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:51
S20	112	vcsel and dbr and (substrate near3 reflect\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 12:06
S21	88	(vcsel and dbr and (substrate near3 reflect\$3)) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:53

S22	0	substrate near3 antireflect\$3 near3 feature\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:55
S23	1423	substrate near3 antireflect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:55
S24	0	(substrate near3 antireflect\$3) and vcsel and dbr	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:55
S25	12	(substrate near3 antireflect\$3) and dbr	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:56
S26	533	(vcsel or (surface near3 emit\$4)) and (specular near3 reflect\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 12:06
S27	1	(substrate near3 antireflect\$3) and ((vcsel or (surface near3 emit\$4)) and (specular near3 reflect\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 11:58
S28	6	(vcsel and dbr and (substrate near3 reflect\$3)) and ((vcsel or (surface near3 emit\$4)) and (specular near3 reflect\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 12:01
S29	70	(vcsel or (surface near3 emit\$4)) and (specular near3 reflect\$3) and (substrate near3 reflect\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 12:41
S30	6	vcsel and dbr and (glare or (specular near3 reflect\$3)) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 12:42
S31	1	"6417901".PN.	USPAT	OR	OFF	2003/08/18 12:46
S32	1	"6233264".PN.	USPAT	OR	OFF	2003/08/18 12:46
S33	1	"5810925".PN.	USPAT	OR	OFF	2003/08/18 12:47
S34	1	"5679152".PN.	USPAT	OR	OFF	2003/08/18 12:47
S35	5	(substrate near3 scat\$7) AND (VCSEL OR (SURFACE NEAR3 emitting)) and dbr	US-PGPUB; USPAT	OR	OFF	2003/08/18 12:50
S36	5	(substrate near3 scat\$7) AND (VCSEL OR (SURFACE NEAR3 emitting)) and dbr	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 12:58

S37	1029	(VCSEL OR (SURFACE NEAR3 emitting)) and dbr	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:02
S38	7	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr) and (glare or (specular near3 reflect\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:00
S39	2	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr) and (substrate near3 antireflect\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:01
S40	934	(VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:03
S41	881	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate) and reflect\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:04
S42	520	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate) and reflect\$4) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:04
S43	122	((VCSEL OR (SURFACE NEAR3 emitting)) and dbr and substrate) and reflect\$4) and "438"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:04
S44	180	(pattern\$3 near3 substrate) and vcsel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:51
S45	0	((pattern\$3 near3 substrate) and vcsel) and reflect\$4 and (specular or diffuse\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 13:53
S46	153	((pattern\$3 near3 substrate) and vcsel) and reflect\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:21
S47	295	vcsel and diffuse\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:21
S48	108	vcsel and diffuse\$1 and dbr and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:21

S49	55	vcSEL and (reflect\$4 near3 (diffuse\$1 or scatter\$3)) and dbr and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:25
S50	265	vcSEL and dbr and substrate	USPAT	OR	OFF	2003/08/18 14:25
S51	197	(vcSEL and dbr and substrate) and "372"/\$.ccls.	USPAT	OR	OFF	2003/08/18 14:26
S52	47	(vcSEL and dbr and substrate) and "438"/\$.ccls.	USPAT	OR	OFF	2003/08/18 14:28
S53	5	vcSEL and dbr and ((grat\$3 or step) near substrate)	USPAT	OR	OFF	2003/08/18 14:32
S54	0	vcSEL and dbr and ((grat\$3) near substrate)	USPAT	OR	OFF	2003/08/18 14:32
S55	2	vcSEL and dbr and ((grat\$3) near substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:33
S56	1	(antireflection near grating) and substrate and dbr	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:35
S57	6	(antireflection near grating) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:39
S58	4106	((specular near3 reflection) or glare) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:41
S59	11	(((specular near3 reflection) or glare) and substrate) and vcSEL	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:41
S60	1782	specular and scattering and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:07
S61	10	(specular and scattering and substrate) and vcSEL	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 14:53
S62	121	specular and scattering and ((textured or rough\$4) near3 substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:27
S63	0	(specular and scattering and ((textured or rough\$4) near3 substrate)) and vcSEL	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:09

S64	121	(specular and scattering and ((textured or rough\$4) near3 substrate)) and (vcSEL or (surface emitting))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:09
S65	72	(semiconductor near3 laser) and (semiconductor near3 substrate) and specular and reflect\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:38
S66	138	(semiconductor near3 substrate) and (specular near reflect\$4) and laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:39
S67	5	((semiconductor near3 substrate) and (specular near reflect\$4) and laser) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:40
S68	24	((semiconductor near3 substrate) and (specular near reflect\$4) and laser) and "438"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:43
S69	127	vcSEL and dbr and substrate and scattering	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:45
S70	7	vcSEL and dbr and substrate and specular	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:45
S71	13	(vcSEL and dbr and substrate and scattering) and "438"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:46
S72	55	(vcSEL and dbr and substrate and scattering) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:52
S73	33	substrate near specular near reflect\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:52
S74	0	(substrate near specular near reflect\$4) and vcSEL	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:53
S75	0	(substrate near specular near reflect\$4) and surface near emitting near laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 15:53

S76	1	vcsl and giro and grating and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:10
S77	0	vcsl and specular and duffuse	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:10
S78	8	vcsl and specular and diffuse	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:10
S79	14	(substrate near grating) and specular and diffuse	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:12
S80	77	(semiconductor near laser) and specular and diffuse	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:13
S81	71	(semiconductor near laser) and specular and diffuse and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:13
S82	1	"6417901".PN.	USPAT	OR	OFF	2003/08/18 16:32
S83	1	"6233264".PN.	USPAT	OR	OFF	2003/08/18 16:32
S84	1	"5679152".PN.	USPAT	OR	OFF	2003/08/18 16:33
S85	1	"5810925".PN.	USPAT	OR	OFF	2003/08/18 16:33
S86	2229	(semiconductor near3 laser) and (pattern\$3 near3 substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:37
S87	208	((semiconductor near3 laser) and (pattern\$3 near3 substrate)) and ((anti adj reflect\$3) or antireflect\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:38
S88	18	((semiconductor near3 laser) and (pattern\$3 near3 substrate)) and ((anti adj reflect\$3) or antireflect\$3)) and specula\$5 and diffus\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 16:40
S89	643	vcsl and (scattering or diffus\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:26
S90	209	(vcsl and (scattering or diffus\$3)) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:24

S91	117	vcsl and ((scattering or diffus\$3) near3 (rays or beam))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:25
S92	23	(vcsl and ((scattering or diffus\$3) near3 (rays or beam))) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:27
S93	226	vcsl and (scattering or diffus\$3) and dbr	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:26
S94	123	(vcsl and (scattering or diffus\$3) and dbr) and "372"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:27
S95	0	subwavelength near substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 17:40
S96	12	subwavelength near structure	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 18:04
S97	4	vcsl near3 leak\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 18:06
S98	2	vcsl and dbr and (grating near substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 18:09
S99	177	vcsl and dbr and (grating and substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 18:09
S10 0	78	vcsl and dbr and grating and substrate and (specular or diffus\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/18 18:10
S10 1	1	"6301281".PN.	USPAT	OR	OFF	2003/08/18 18:19
S10 2	1	"6031243".PN.	USPAT	OR	OFF	2003/08/18 18:19
S10 3	1	"6002705".PN.	USPAT	OR	OFF	2003/08/18 18:19
S10 4	1	"5995531".PN.	USPAT	OR	OFF	2003/08/18 18:19

S105	8	(surface near3 texture\$1) and vcsel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/19 14:59
S106	0	(antireflect\$3 near3 layer) and vcsel and substrate and dbr	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/19 15:01
S107	15	(antireflect\$3 near3 layer) and vcsel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/19 15:05
S108	144	(edge near emitting near laser) and vcsel and dbr and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/19 15:06
S109	165	led and vcsel and dbr and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2003/08/19 15:07
S110	424	vcsel and substrate near3 reflect\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/07 18:30
S111	214	vcsel and substrate near3 reflect\$3 and "372"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/01/07 18:30